

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Fischer et al.

Application No: 10/077,072

Filed: February 14, 2002

For: A Plasma Processing
Apparatus and Method for Confining
An RF Plasma Under Very High Gas
Flow and RF Power Density Conditions
(As Amended)



Docket: P0877

Group: 2821

Examiner: Lee, Wilson

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I hereby certify that this paper is being deposited with the
United States Postal Service "First Class Mail" service
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Washington, D.C. 20231 on March 26, 2003.

Sharon Tillery
Sharon Tillery

AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir or Madam:

In response to the Office Action mailed on 12/4/2002, Applicant submits the
following amendment.

In the Specification

To clarify the invention, the Applicant makes a small modification to the
Specification that does not add new matter. The support for the modification is
described in further detail below in the REMARKS section.

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